# **Electronic Supplementary Information**

# Copper (I) sulfide: A two-dimensional semiconductor with superior oxidation resistance and high carrier mobility

Yu Guo,<sup>ab</sup> Qisheng Wu,<sup>bc</sup> Yunhai Li,<sup>c</sup> Ning Lu,<sup>d</sup> Keke Mao,<sup>be</sup> Yizhen Bai,<sup>a</sup> Jijun Zhao,<sup>\*a</sup> Jinlan Wang<sup>\*cf</sup> and Xiao Cheng Zeng <sup>\*bg</sup>

<sup>a</sup>Key Laboratory of Materials Modification by Laser, Ion and Electron Beams (Dalian University of Technology), Ministry of Education, Dalian, Liaoning 116024, China

<sup>b</sup>Department of Chemistry, University of Nebraska–Lincoln, Lincoln, Nebraska 68588, United States

<sup>c</sup>School of Physics, Southeast University, Nanjing, Jiangsu 211189, China

<sup>d</sup>Anhui Province Key Laboratory of Optoelectric Materials Science and Technology, Department of Physics, Anhui Normal University, Wuhu, Anhui 241000, China

<sup>e</sup>School of Energy and Environment Science, Anhui University of Technology, Maanshan, Anhui 243032, China

<sup>f</sup>Synergetic Innovation Center for Quantum Effects and Applications (SICQEA), Hunan Normal University, Changsha, Hunan 410081, China

<sup>g</sup>Department of Chemical & Biomolecular Engineering and Department of Mechanical & Materials Engineering, University of Nebraska–Lincoln, Lincoln, Nebraska 68588, United States

<sup>\*</sup>Corresponding authors: zhaojj@dlut.edu.cn (J. Zhao); jlwang@seu.edu.cn (J. Wang); xzeng1@unl.edu (X. C. Zeng)



S1. Geometric structures, dynamical and thermal stability of selected Cu2S monolayers

**Fig. S1**. (a) Four representative low-energy structures of freestanding Cu<sub>2</sub>S monolayer predicted by using the CALYPSO code. The unit cells are denoted by dashed lines. Cu and S atoms are shown in pink and yellow, respectively. (b) Corresponding phonon dispersions of the four polymorph structures. High-symmetry points of the first Brillouin zone are:  $\Gamma$  (0, 0, 0), X (0.5, 0, 0), Y (0, 0.5, 0) and Q (0.5, 0.5, 0). Among four structures, only Cu<sub>2</sub>S-0 ( $\delta$ -Cu<sub>2</sub>S) and Cu<sub>2</sub>S-2 are dynamically stable.

**Table S1**. Formation energies ( $\Delta H$ ) of four Cu<sub>2</sub>S monolayer structures shown in Fig. S1.

System	$Cu_2S-0$ ( $\delta$ - $Cu_2S$ )	Cu <sub>2</sub> S-1	Cu <sub>2</sub> S-2	Cu <sub>2</sub> S-3
$\Delta H$ (eV/atom)	-0.21	-0.13	0.05	0.07



Fig. S2. Snapshots structures of the  $\delta$ -Cu<sub>2</sub>S (a) and Cu<sub>2</sub>S-2 monolayers (b) after 10 ps Born-Oppenheimer molecular dynamic simulations, with the temperature being controlled at 300 K. Cu and S atoms are shown in pink and yellow, respectively.

#### S2. Geometric and electronic structures of β-Cu<sub>2</sub>S bilayer



**Fig. S3**. (a) Top and side views of the experimentally fabricated  $\beta$ -Cu<sub>2</sub>S bilayer (see *Adv. Mater.* **2016**, 28, 8271–8276). (b) Band structure of  $\beta$ -Cu<sub>2</sub>S bilayer with a direct band gap (E<sub>g</sub>) at  $\Gamma$  point, computed based on PBE (left panel) and HSE06 level (right panel), respectively. The Fermi level is set to zero.

S3. Snapshots of  $\delta$ -Cu<sub>2</sub>S monolayer taken at the end of each Born-Oppenheimer molecular dynamics (BOMD) simulation



Fig. S4. Structure snapshots of  $\delta$ -Cu<sub>2</sub>S monolayer from BOMD simulations with temperature being controlled at (a) 300, (b) 500, (c) 800, and (d) 900 K, respectively. Each simulation lasts for 10 ps.

#### S4. Several adsorption sites for $O_2$ on $\delta$ -Cu<sub>2</sub>S



Fig. S5. Top and side views of local geometries for several other adsorption sites for  $O_2$ . The number at the bottom indicate the binding energy of  $O_2$  adsorption on  $\delta$ -Cu<sub>2</sub>S. Since  $O_2$  chemisorption on  $\delta$ -Cu<sub>2</sub>S exhibits only one configuration (see Fig. 3), the structures of  $O_2$  physisorbed on  $\delta$ -Cu<sub>2</sub>S are shown here.

# S5. Chemical stability of $\delta$ -Cu<sub>2</sub>S monolayer considering experimental O<sub>2</sub> bonding energy

**Table S2.** A comparison of energies for initial  $(E^i)$ , transition  $(E^i)$  and final  $(E^f)$  states, activation energy  $(E^a)$ , and heat of reaction  $(E^H)$  with either the experimental or DFT calculated O<sub>2</sub> bonding energy as the reference. The unit of  $E^i$ ,  $E^t$ ,  $E^f$ ,  $E^a$  and  $E^H$  is eV.

	$E^i$	$E^t$	Eſ	E <sup>a</sup>	$E^H$
Exp.	-1.74	0.24	-1.82	1.98	0.08
DFT	-0.09	1.89	-0.17	1.98	0.08



## S6. BOMD simulations of O<sub>2</sub> collision with $\delta$ -Cu<sub>2</sub>S monolayer at 300 K

Fig. S6. Snapshots of BOMD simulations of  $O_2$  oxidation at 300 K at 1 - 5 ps. It can be seen that  $O_2$  molecules are typically bounced back to the vacuum after collision with the  $\delta$ -Cu<sub>2</sub>S monolayer. Hence, it seems that  $\delta$ -Cu<sub>2</sub>S monolayer exhibits superior oxidation resistance.



## S7. Strain effect on the band structure of $\delta$ -Cu<sub>2</sub>S monolayer

Fig. S7. Band structures of  $\delta$ -Cu<sub>2</sub>S monolayer under various lateral strain from -3% to 3%, computed based on HSE06 functional. Fermi levels are set to zero. E<sub>g</sub> is the band gap denoted by the solid arrow.



Fig. S8. Strain effect on the band gap of  $\delta$ -Cu<sub>2</sub>S monolayer calculated based on the HSE06 functional.